

	Hits	Search Text	DBs
47	22	((heat\$4 or anneal\$7 or bak\$4 or cur\$4 or post\$5heat\$4 or thermal\$4 or solidifying or solidification or solidify) same (pattern or mask or stencil\$3 or frame) same (trench\$4 or hole or opening or via) same (liquid or solution) same (material or solute or compound or substance) same (atomiz\$6 or deposit\$4 or coat\$4) same (organometallic or (conductive near12 organic)))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
48	13	((heat\$4 or anneal\$7 or bak\$4 or cur\$4 or post\$5heat\$4 or thermal\$4 or solidifying or solidification or solidify) same (pattern or mask or stencil\$3) same (trench\$4 or hole or opening or via or through\$4hole) same (liquid or solution) same (material or solute or compound or substance pr precursor) same (atomiz\$6 or deposit\$4 or spray\$5coat\$4 or spin\$4coat\$4) same (organometallic or (conductive near12 organic)))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
49	21	((pattern or mask or stencil\$3 or frame) same (trench\$4 or hole or opening or via) same (liquid or solution) same (material or solute or compound or substance) same (atomiz\$6 or deposit\$4 or coat\$4) same (organometallic or (conductive near12 organic))) and ((heat\$4 or anneal\$7 or bak\$4 or cur\$4 or post\$5heat\$4 or thermal\$4 or solidifying or solidification or solidify) same (precursor or liquid or solution) same (conductive or metal\$4 or organometallic) same (evaporat\$4 or anneal\$4))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
50	75	((pattern or mask or stencil\$3) same (trench\$4 or hole or opening or via or through\$4hole) same (liquid or solution or precursor) same (atomiz\$6 or deposit\$4 or coat\$4 or fill\$4) same (organometallic or (conductive near12 organic) or (metal\$4 near7 organic))) and ((heat\$4 or anneal\$7 or bak\$4 or cur\$4 or post\$5heat\$4 or thermal\$4 or solidifying or solidification or solidify) same (precursor or liquid or solution) same (conductive or metal\$4 or organometallic) same (evaporat\$4 or anneal\$4))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
51	21	((pattern or mask or stencil\$3 or frame) same (trench\$4 or hole or opening or via) same (liquid or solution) same (material or solute or compound or substance) same (atomiz\$6 or deposit\$4 or coat\$4) same (organometallic or (conductive near12 organic))) and ((heat\$4 or anneal\$7 or bak\$4 or cur\$4 or post\$5heat\$4 or thermal\$4 or solidifying or solidification or solidify) same (precursor or liquid or solution) same (conductive or metal\$4 or organometallic) same (evaporat\$4 or anneal\$4))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
52	54	S63 NOT S64	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
53	19	((pattern or mask or stencil\$3) same (trench\$4 or hole or opening or via or through\$4hole) same (liquid or solution or precursor) same (print\$4) same (organometallic or (conductive near12 organic) or (metal\$4 near7 organic))) and ((heat\$4 or anneal\$7 or bak\$4 or cur\$4 or post\$5heat\$4 or thermal\$4 or solidifying or solidification or solidify) same (precursor or liquid or solution) same (conductive or metal\$4 or organometallic) same (evaporat\$4 or anneal\$4))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB